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	STATEMENT BY APPLICANT			
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		Applicant:		
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7 1.	Kouvetakis, et al., U.S. Patent Application No. 10/559,980, Filed on December 8, 2005.			
2.	Kouvetakis, et al., U.S. Patent Application No. 10/559,981, Filed on September 5, 2006 (Projected Publication date is January 11, 2007).			
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